

Notice of References CitedApplication/Control No.
09/249,728Applicant(s)/Patent Under
Reexamination
LOPEZ ET AL.Examiner
Mehrddad DastouriArt Unit
2623

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U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-			
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FOREIGN PATENT DOCUMENTS

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NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Budd et al, "Development and Application of a New Tool for Lithographic Mask Evaluation, the Stepper Equivalent Aerial Image Measurement System (AIMS)", 1997, IBM Journal of Research and Development, Vol. 41, No. 1/2
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